

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In Re Application of:

Robert David Allen et al.

Confirmation No.: 2060

Serial No.: 10/729,452

Group Art Unit: 1752

Filing Date: December 4, 2003

Examiner: John S.Y. Chu

Title: METHOD FOR PATTERNING A LOW ACTIVATION ENERGY PHOTORESISTS

**AMENDMENT UNDER 37 C.F.R. § 1.111**

**Mail Stop Amendment**

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

Responsive to the non-final Office Action mailed on September 19, 2006, please reconsider this application in view of the amendments and remarks set forth in this paper. As this paper is timely filed within the three-month shortened statutory period for response, no fee accompanies this paper.

**LISTING OF THE CLAIMS:**

The amendments to the claims are reflected in the listing of the claims set forth on pages 2 to 10 of this paper.

**REMARKS:**

Applicants' comments in support of this application are presented in the remarks set forth on page 11 of this paper.